

**LITHOGRAPHIC PHOTOMASK AND METHOD OF MANUFACTURE TO  
IMPROVE PHOTOMASK TEST MEASUREMENT**

**ABSTRACT OF THE DISCLOSURE**

5           A photomask for use in a lithographic process and a method of making a  
photomask are disclosed. A mask blank including a substrate, a sacrificial  
conductive layer disposed over the substrate and a radiation shielding layer  
disposed over the sacrificial conductive layer can be provided. Structures are  
then formed from the radiation shielding layer to define a pattern. Measurement  
10 of parameters associated with the structures are made with a measurement tool  
and, during the measuring, the sacrificial conductive layer provides a conductive  
plane to dissipate charge transferred to the mask by the measurement tool.

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